



#8/Election
PATENT APPLICATION

OCT 22 2001 10/23/01

TECHNOLOGY CENTER 2800

THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Kyoichi SUWA

Group Art Unit: 2818 Smith

Application No.: 09/729,339

Examiner: Q. Hoang

Filed: December 5, 2000

Docket No.: 108057

For: MASK, EXPOSURE METHOD, LINE WIDTH MEASURING METHOD, AND
METHOD FOR MANUFACTURING SEMICONDUCTOR DEVICES

RESPONSE TO RESTRICTION REQUIREMENT

Director of the U.S. Patent and Trademark Office
Washington, D.C. 20231

Sir:

In reply to the Restriction Requirement mailed October 5, 2001, Applicant hereby provisionally elects Group I, claims 1-8 and 11-14. This election is made with traverse.

It is respectfully submitted that the subject matter of all claims 1-14 is sufficiently related that a thorough search for the subject matter of Group I would necessarily encompass a search for the subject matter of Group II. Thus, it is respectfully submitted that the search and examination of the entire application could be made without serious burden. MPEP §803 states that "[i]f the search and examination of the entire application can be made without serious burden, the Examiner must examine it on the merits, even though it includes claims to distinct or independent inventions" (emphasis added). It is respectfully submitted that this policy should apply in the present application in order to avoid unnecessary delay and expense to Applicant and duplicative examination by the Patent Office.

The Examiner is respectfully requested to reconsider and withdraw the Restriction Requirement and to examine all the claims in this application.

Respectfully submitted,



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Date: October 18, 2001

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